PECVD-SiN	Date	wafer#	LPD count before	LPD after 5min pump down	LPD after SiN deposition	Thickness	Index
	PM-5-9-2012						
	5/14/12	wafer#1	224		283	1072.30A	n=1.961
	5/14/12	wafer#2	315		2843*	3189.83A	n=1.954
comment:	* Cleaning not done between depositions, added a lot of small particles						
	5/21/12	wafer#3	85	80	144	1059.30	n=1.959
		wafer#4	123	108	184	1063.03	n=1.960
	PM-6-1-2012						
	6/5/12	wafer#5	656	603	698	1090.90A	n=1.967
		wafer#6	413	419	501	1105.12A	n=1.969
		wafer#7	543	161	not done deposition		
	6/15/12	wafer#8	164	not done	4868**	2977.50A	n=1.962
comment:	** A lot of small particles						
	6/19/12	wafer#9	220	151			
		wafer#10	286	309			
		wafer#11	234	240	348*	1042.52A	n=1.964
comment:	* few groups of small particles						